

## \*\*COMPLETE THIS FORM TO INITIATE SUPPLIER SCOUTING\*\* MEPNN Supplier Scouting Opportunity Synopsis

\*The submitting entity agrees to notify NIST MEP of the status of actions taken as a result of this scouting instance within 30 days after receiving a results report. For instances where the submitting entity is an MEP Center submitting on behalf of a client, the MEP Center agrees to notify NIST MEP on behalf of their client. For instances where the submission is direct from federal/state agencies or is a private company, the submitting federal/state agency or private company entity agrees to notify NIST MEP. Notification should be via email to <a href="mailto:scouting@nist.gov">scouting@nist.gov</a>, indicating the following:

- Contact with matches identified in report complete and supply contract awarded, process complete
- Contact with matches identified in report complete and no supply contract awarded, process complete
- Contact with matches identified in report complete and supply negotiations underway, process in progress
- Contact with matches identified in report underway; supply negotiations not yet begun; process in progress
- · Contact with matches identified in report not yet begun, process in progress
- Contact with matches identified in report will not occur within the next 6-months, process complete

Wafer bonder and li	ithography	aligner	system

days
Opportunities will be postedfor 30 days unless specified

Item to be Scouted

Please describe the item application/ the end use of item.\* Provide the item number if applicable: (N95 Mask vs Protective Mask).

The National Institute of Standards and Technology (NIST) seeks information on commercial vendors that are capable of providing a wafer bonder and lithography aligner system to support nanofabrication in the Center for Nanoscale Science and Technology (CNST) user facility. The system will be sitted and used as a shared resource accessible to researchers from industry, academia, NIST, and other government agencies in the CNST NanoFab. Wafer bonder is a unique fabrication tool that bring two wafers adhere to each other without the application of any macroscopic gluing layer or external mechanical force. It produces a mechanically stable interface and hermetically sealed encapsulation between two wafers. Bonding alignment is the precedent step before the actual wafer bonding. It places two substrates in particular positions relative to each other in order to combine the functions of both substrates. The bonding alignment can be performed by the wafer bonder itself or by a compatible lithography aligner.

2022		Number (NICT MED use)
		Number (NIST MEP use)
3332		
	custome	r/product <u>NAICS Code</u> , if known
TE		a. Type of supplier being sought*           Image: Manufacturer         Image: Contract Manufacturer         Image: Distributor
HCH	Sup	
	Supplier	Other
TECHNICAL INFORMATION:		b. Reason for scouting submission*
NFO	Informatior	□ 2 <sup>nd</sup> Supplier □ Price □ Re-shore □ Past supplier no longer available
	mat	
TAN	ion	New Product Startup
Ō		Other
· · ·		a. Describe the manufacturing processes (elaborate to provide as much detail as possible).*
	2. S	a. Describe the manufacturing processes (elaborate to provide as much detail as possible).
	2. Summary of Te and Performance	Item needed as one standalone unit
	hary	
	of	b. Provide dimensions / size / tolerances / performance specifications for the item.*
		A lithography aligner does wafer exposure for pattern transferring purpose as well as alignment for lithography and bonding purposes. Its main components include a UV light source, beam shaping optical lens, wafer positioning system with top and bottom sides of
	chr Rec	microscopes for the upper and lower wafers. For bonding purpose it shall also have a securing mechanism for the wafer stacks in order to
		transport aligned wafer pair into wafer bonder without introducing the alignment shift. Applications include fabricating nano-semiconductor and nano-photonic devices. The NanoFab currently operates an outdated wafer bonder and lithography aligner system which is more than
	S	15 years old. After years of extreme thermal cycles and usage, mechanical fatigue has caused certain crucial components losing functions
	pec ent	or precision. In the past five years, considerate amount of manpower was put in to maintain this system in usable condition and some replacement parts have been difficult to acquire. In order to increase NIST's capacity to serve users and provide additional technical
	fic:	capabilities for nanofabrication, NIST has a need for a new wafer bonder and lithography aligner system. The system must be equipped
	atio	with following components: 1. Wafer Bonder configuration: 1) The system shall be able to transfer and process substrates with various shapes and sizes from 10 mm to 150 mm. 2) The system shall be able to process substrates with thickness 9 mm or larger. 3) The
	SI	process chamber shall be able to perform controlled heating and cooling. 4) The heating system shall support the minimum heating
		temperature of 500 °C. 5) The system shall be capable of applying voltage on the wafer stacks for anodic bonding. 6) The process

	MEP Natio	
		chamber shall have 2 or more gas ports available. 7) A pumping system for process chamber shall be able to do overpressure and vacuuming down to 1x10-5 Torr. 8) The system shall have substrate holders supporting bonding alignment of 75 mm, 100 mm and 150 mm diameters of wafers. 9) Software that supports both manual and automatic operations. 10) The system shall be provided with a computer to perform interface, control, and logging functions. 11) Safety interlocks for the chamber door. 2. Lithography aligner configuration: 1) The system shall be able to process substrates with various shapes and sizes from 10 mm to 150 mm. 2) The system shall be able to process substrates with various shapes and sizes from 10 mm to 150 mm. 2) The system shall be able to process substrates with various shapes and sizes from 10 mm to 150 mm. 2) The system shall be able to process substrates with various shapes and sizes from 10 mm to 150 mm. 2) The system shall be able to process substrates with thickness 5 mm or larger. 3) The system shall buply the exposure light source including 405 nm and 365 nm wavelength with sufficient illumination power for 50 µm or thicker broadband photoresist. 4) The system shall be able to expose 1 um thick photoresist with a resolution of 1 um or smaller. 5) The system shall be able to align the frontside of a wafer to a photomask with the alignment accuracy 0.5 um or better and the backside of a wafer to a photomask with alignment accuracy 1 um. 6) Software shall be able to perform pattern recognition on alignment marks for semiautomatic alignment while still allows manual alignment accuracy 2. The system shall be able to align the chanical transferring into the compatible wafer bonder is required. 9) The system shall have safety interlocks in the illumination housing and proper UV light shielding for operators.
	2. Sun	d. Are there applicable certification requirements?*
	2. Summary of Technical Specifications and Pe cont:	e. Are there applicable regulations?*  Yes No Please explain
		f. Are there any other standards, requirements, etc.?*  Yes No Please explain
	Performance	g. Additional Comments: Is there other information that would impact the item's performance or usefulness? Please explain.
	Requirements	
BU	3. V Prio	3a. Estimated potential business volume (i.e., # Units Per Day, Month, Year)*:
BUSINESS INFORMATION:	3. Volume and Pricing	One unit
VFOR	d	b. Estimated target price / unit cost information (flexible and negotiable not accepted) *:
RMAT		\$1,300,000.00
ION:	4. D. Req	a. When is it needed by? (Immediate, 30 Days, 6 months, etc.)*
	4. Delivery Requirements:	ASAP b. Describe packaging requirements (i.e., individually/group packaging)*
	nents	
	÷	Flexible



	c. Where will this item be shipped?*
	NIST, 100 bureau Drive, Gaithersburg, MD 20899
5. A	Is there other information you would like to include?
Additional	
Comments:	
nts:	_

Photos or diagrams of the item (helpful but not required).